

FORM PTO-1449 (Modified)  
U.S. Department of Commerce, Patent and Trademark Office

Docket No.

Serial No.

99-102/1D

## INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use several sheets if necessary)

Applicants

Wilbur G. Catabay et al.

Filing Date  
HerewithGroup  
2813

U.S. PRO  
10/099641  
03/15/02

## U.S. Patent Documents

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
WAC	AA	5,874,367	2/23/99	Dobson	438	787	12/28/94
↑	AB	5,904,154	5/18/99	Chien et al.	134	1.2	7/24/97
	AC	5,882,489	3/16/99	Bersin et al.	204	192.35	4/26/96
	AD	5,858,879	1/12/99	Chao et al.	438	725	6/6/97
	AE	3,012,861	12/12/61	Ling	23	223.5	1/15/60
	AF	3,178,392	4/13/65	Kriner	260	46.5	4/9/62
	AG	3,832,202	8/27/74	Ritchie	106	287	8/8/72
	AH	3,920,865	11/18/75	Läufer et al.	427	220	4/6/72
↓	AI	4,705,725	11/10/87	Glajch et al.	428	405	11/28/86
	AJ	5,194,333	3/16/93	Ohnaka et al.	428	405	12/18/90
WAC	AK	5,874,745	2/23/99	Kuo	257	59	8/5/97

## Foreign Patent Documents

## Translation

		Document Number	Date	Country	Class	Subclass	Yes	No
WAC	AL	DE 198 04 375 A1	7/1/99	Germany	H 01 L	21/312		X
↑	AM	EP 0 706 216 A2	4/10/96	Europe	H 01 L	23/532	N/A	
	AN	EP 0 949 663 A2	10/13/99	Europe	H 01 L	21/312	N/A	
↓	AO	63003437	1/8/88	Japan	H 01 L	21/90	X-Abstract Only	
WAC	AP	WO 99/41423	8/19/99	PCT	C 23 C		N/A	

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

WAC	AR	Bothra, S., et al., "Integration of 0.25 $\mu$ m Three and Five Level Inter-connect System for High Performance ASIC", 1997 Proceedings Fourteenth International VMIC Conference, Santa Clara, CA, June 10-12, 1997, pp.43-48.
WAC	AS	Dobson, C.D., et al., "Advanced SiO <sub>2</sub> Planarization Using Silane and H <sub>2</sub> O <sub>2</sub> ", Semiconductor International, December 1994, pp. 85-88.
WAC	AT	McClatchie, S., et al., "Low Dielectric Constant Oxide Films Deposited Using CVD Techniques", 1998 Proceedings Fourth International DUMIC Conference, February 16-17, 1998, pp. 311-318.

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WAC	AA	6,066,574	5/23/00	You et al.	438	781	11/6/98
	AB	6,051,477	4/18/00	Nam	438	404	10/22/96
	AC	6,025,263	2/15/00	Tsai et al.	438	624	9/11/97
	AD	5,939,763	8/17/99	Hao et al.	257	411	9/5/96
	AE	5,864,172	1/26/99	Kapoor et al.	257	634	8/13/96
	AF	5,688,724	11/18/97	Yoon et al.	437	235	12/23/94
	AG	5,470,801	11/28/95	Kapoor et al.	437	238	6/28/93
	AH	5,364,800	11/15/94	Joyner	437	28	6/24/93
	AI	4,771,328	9/13/88	Malaviya et al.	357	49	11/24/86
	AJ	3,652,331	3/28/72	Yamazaki	117	201	3/13/69
WAC	AK	6,153,524	11/28/00	Henley et al.	438	691	7/28/98

## Foreign Patent Documents

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	AL							
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	AP							

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

WAC	AR	Peters, Laura, "Pursuing the Perfect Low-k Dielectric", <u>Semiconductor International</u> , Vol. 21, No. 10, September, 1998, pp. 64-66, 68, 70, 72, and 74.
WAC	AS	Koda, Seiichiro, et al., "A Study of Inhibition Effects for Silane Combustion by Additive Gases", <u>Combustion and Flame</u> , Vol. 73, No. 2, August, 1988, pp. 187-194.
WAC	AT	Sugahara, Satoshi, et al., "Chemical Vapor Deposition of CF <sub>3</sub> -Incorporated Silica Films for Interlayer Dielectric Application", 1999 Joint International Meeting, <u>Electrochemical Society Meeting Abstracts</u> , Vol. 99-2, 1999, Abstract No. 746.

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WAC	AA	6,051,073	4/18/00	Chu et al.	118	723	6/3/98
↑	AB	5,580,429	12/3/96	Chan et al.	204	192.38	6/7/95
	AC	5,558,718	9/24/96	Leung	118	723E	4/8/94
	AD	5,628,871	5/13/97	Shinagawa	438	514	6/24/94
	AE	6,028,015	2/22/00	Wang et al.	438	789	3/29/99
	AF	6,114,259	9/5/00	Sukharev et al.	438	789	7/27/99
	AG	6,147,012	11/14/00	Sukharev et al.	438	787	11/12/99
	AH	6,204,192	3/20/01	Zhao et al.	438	723	3/29/99
	AI	6,232,658	5/15/01	Catabay et al.	257	701	6/30/99
	AJ	6,037,248	3/14/00	Ahn	438	619	6/13/97
WAC	AK	5,675,187	10/7/97	Numata et al.	257	758	5/16/96

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LAC	AA	5,559,367	9/24/96	Cohen et al.	257	77	7/12/94
↑	AB	5,376,595	12/27/94	Zupancic et al.	501	12	8/28/92
	AC	6,043,167	3/28/2000	Lee et al.	438	789	10/10/97
	AD	5,314,845	5/24/94	Lee et al.	437	238	2/2/90
	AE	5,915,203	6/22/99	Sengupta et al.	438	669	6/10/97
	AF	6,054,379	4/25/2000	Yau et al.	438	623	2/11/98
	AG	5,989,998	11/23/99	Sugahara et al.	438	623	8/28/97
↓	AH	6,215,087	04-2001	Akahori et al.	219	121.43	6/16/98
LAC	AI	6,303,047	10/16/01	Aronowitz et al.	252/1	106/287.13	3/22/99
	AJ						
	AK						

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Wilbur G. Catabay et al.

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March 15, 2002

Group

Unknown

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	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

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	AN							
	AO							
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